

	Hits	Search Text	DBs
29	0	(non\$4ionic\$4surfactant same ((phenol near14 ethoxylate) or (polyoxyethylene near12 monoalkyl near8 ether)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
30	238	((non\$4ionic\$4surfactant or (surface near5 active near5 agent)) same ((phenol near14 ethoxylate) or (polyoxyethylene near12 monoalkyl near8 ether)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
31	65	((non\$4ionic\$4surfactant or (surface near5 active near5 agent) or surfactant) same ((phenol near4 ethoxylate) or (polyoxyethylene near4 monoalkyl near4 ether)) same (resist or photoresist or photosensitive))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
32	100	((non\$4ionic\$4surfactant or (surface near5 active near5 agent) or surfactant) same ((phenol near14 ethoxylate) or (polyoxyethylene near12 monoalkyl near8 ether)) same (apply\$4 or coat\$4 or layer or film)) and (photosensitive or photoresist or resist)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
33	34	((non\$4ionic\$4surfactant or (surface near5 active near5 agent) or surfactant) same ((phenol near14 ethoxylate) or (polyoxyethylene near12 monoalkyl near8 ether)) same (apply\$4 or coat\$4 or layer or film)) and ((photosensitive or photoresist or resist) near12 pattern)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB